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PATENT  
30205/39719

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application of: Seong Hwan Park et al. )  
Serial No.: 10/718,277 )  
Filed: November 20, 2003 )  
For: Photoresist Removing )  
Compositions )  
Group Art Unit: 1752 )  
Examiner: Hoa Van Le )  
I hereby certify that this paper and the  
documents referred to as enclosed  
therewith are being deposited with the  
United States Postal Service as first class  
mail, postage prepaid, on September 30,  
2004, in an envelope addressed to  
Commissioner for Patents, P.O. Box  
1450, Alexandria, Virginia 22313-1450  
\_\_\_\_\_  
Michael R. Hull  
Reg. No. 35,902  
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## COMMENT ON STATEMENT OF REASONS FOR ALLOWANCE

Commissioner for Patents  
P.O. Box 1450  
Alexandria, Virginia 22313-1450

Sir:

In addition to the reasons for allowance set forth in the allowance papers that were mailed in connection with the present application, it is respectfully submitted that the claims are allowable for the additional reasons that the invention defined by the language of the claims is neither anticipated by, nor would have been obvious when taken as a whole in view of, the art of record.

Respectfully submitted,

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September 30, 2004

By: